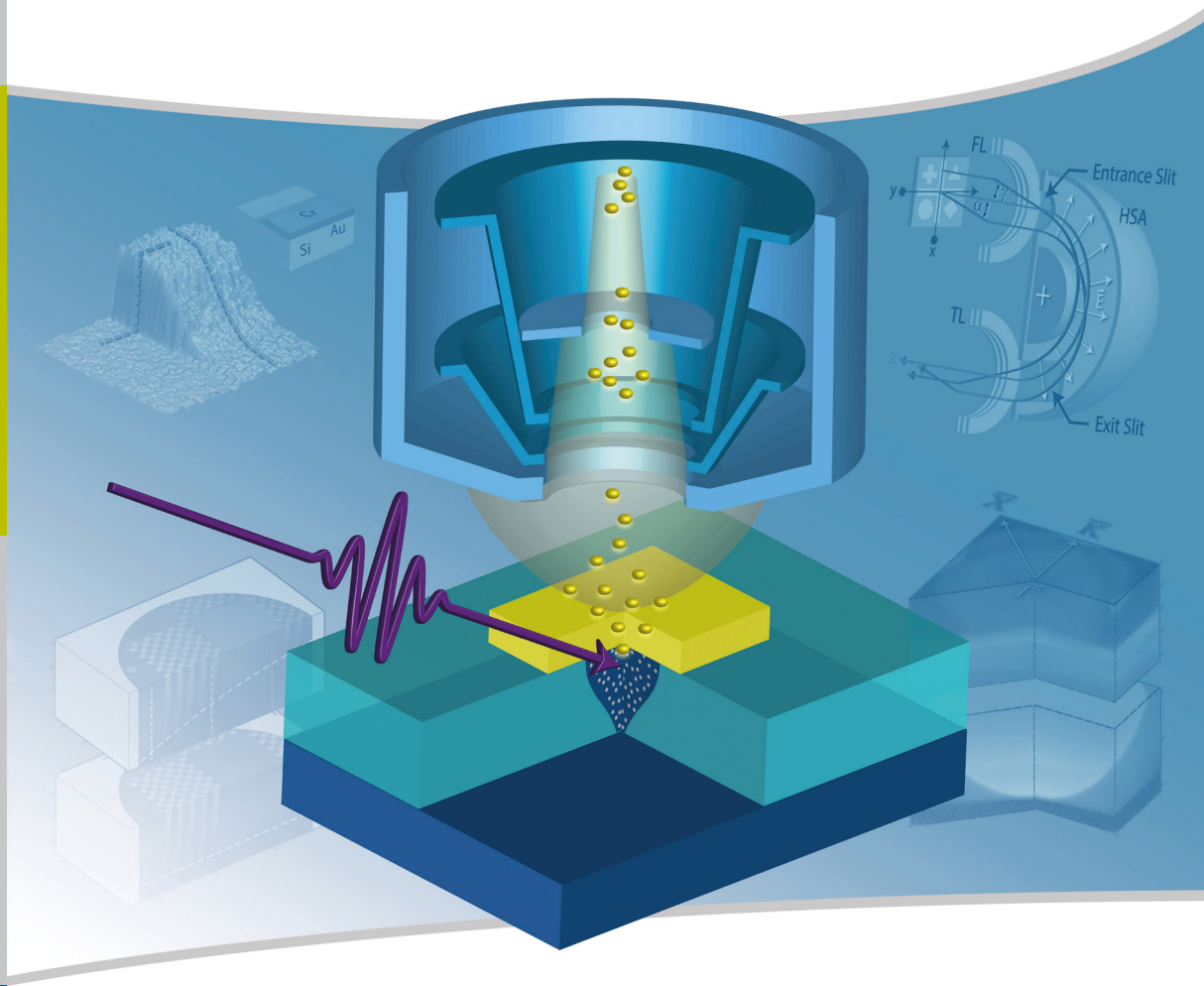
Bulk and surface sensitive energy-filtered photoemission microscopy using synchrotron radiation for the study of resistive switching memories

Marten Christopher Patt



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Contents

1. Introduction **1**

2. Fundamental aspects of energy-filtered photoemission microscopy **7**

2.1. Photoemission spectroscopy 10

2.1.1. Penetration of the incoming photons and photo-ionization cross section 13

2.1.2. The photo-excitation process 14

2.1.3. Photoelectron transport to the surface and inelastic mean free path 17

2.1.4. Transmission through the surface and momentum conservation 19

2.2. Angular and momentum resolved photoemission 21

2.3. X-ray absorption spectroscopy 23

2.4. Work function 24

2.4.1. Work function and contact potential 25

2.4.2. Influence of an accelerating field 26

2.5. Conclusions 28

3. Instrumental aspects **29**

3.1. Instrumental aspects of the NanoESCA microscope 30

3.1.1. The objective 30

3.1.2. The Projection column 32

3.1.3. The energy filter 33

3.1.4. The image detection 37

3.1.5. The channeltron detection 39

3.1.6. Photoemission microscopy and momentum microscopy 39

3.2. Light sources 41

3.2.1. UV excitation 41

3.2.2. Soft X-ray and hard x-ray synchrotron sources 43

3.3. Conclusions 47

4. Evaluation methods **49**
4.1. Work function analysis 50
4.1.1. About the nature of the work function edge 50
4.1.2. Fit model for the work function edge 52
4.1.3. The fitting procedure 55
4.1.4. Applicability and robustness of the procedure 55
4.2. Principal Component Analyis 56
4.3. Conclusions 58

5. Objective lens calculations **59**
5.1. Basic calculations 59
5.1.1. Electron kinetics between sample and extractor 60
5.1.2. Conversion from the electron emission angle α to the microscope entrance angle α' 64
5.1.3. Estimation of relativistic corrections 65
5.2. Acceptance angle of the objective lens 66
5.2.1. Relation between contrast aperture and energy analyzer entrance slit 68
5.3. Transmission of the objective lens 70
5.4. Spatial resolution of the objective lens 73
5.4.1. Spherical aberration of the accelerating field 75
5.4.2. Chromatic aberration of the acceleration field 78
5.4.3. Aberrations of the objective lens 79
5.4.4. Diffraction at the contrast aperture 81
5.4.5. The total aberration of the objective 84
5.5. Conclusions 85

6. Non - Isochromaticity of the Energy Filter **89**
6.1. Non-Isochromaticity analysis and correction 90
6.1.1. Impact of the energy shift on the intensity distribution of a photoemission image 90
6.1.2. Determination of the energy shift by a work function analysis 92
6.1.3. Energy shift correction of the image spectrum 94
6.2. Energy filter calculations 96
6.2.1. The set of transfer functions to calculate the electron trajectories 96
6.2.2. Calculating the electron trajectories passing the filter 97
6.2.3. Analysis of the calculated trajectories 100

6.2.4. Simulation of energy-filtered PEEM images 102
6.2.5. The footprint of the non-isochromaticity in energy-filtered images 103
6.3. Calibration of the intermediate image plane 107
6.3.1. Magnification of the intermediate image plane 108
6.3.2. Non-Isochromaticity dependence on the projective magnification 109
6.4. Experimental characterization of the Non-isochromaticity 114
6.4.1. Effects of the analyzer pass-energy and slit configuration . . . 115
6.4.2. An interpretation of the energy-shift dependencies 119
6.5. A generalized fit model for the intensity shift 123
6.6. Conclusions 124

7. Instrumental characterization measurements **127**
7.1. Detection of the photoelectrons 127
7.1.1. Flat field, Dark field and Image-Correction in the analogue imaging mode 128
7.1.2. Image intensity and its dependency on the MCP voltage . . . 129
7.1.3. Single Event Counting 133
7.2. Momentum microscopy and k-Calibration 136
7.2.1. Calibration of the $k_{\parallel}$ scale with the photoemission horizon . . 141
7.2.2. Energy resolution 142
7.2.3. Relation between the contrast aperture and the momentum space 144
7.3. Spatial resolution in spectro-microscopy 146
7.3.1. A test sample for spatial resolution 146
7.3.2. Microspectroscopy and chemical analysis 150
7.4. Conclusions 154

8. Hard x-ray photoemission electron microscopy **157**
8.1. Preliminary aspects of HAXPEEM experiments 157
8.1.1. Experimental peculiarities 157
8.1.2. Sample design 159
8.2. Work function analysis with high kinetic photoelectrons 160
8.3. Space-Charge influence on the spatial resolution 167
8.4. Bulk sensitive imaging and chemical imaging 171
8.5. Accessing buried interfaces 176
8.5.1. EAL determination 178
8.5.2. Lateral Resolution and Probing Depth 183
8.6. Conclusions 185

9. Outlook: Towards time-resolved device analysis **187**
9.1. First HAXPEEM results on STO 188
9.2. Towards time resolved studies 190

10. Summary **195**

A. Often used equations **199**
A.1. Gauss/Step-Function 199
A.2. Spatial Calibration 199
A.3. Spectral fits with a Voigt profile 201
A.4. Energy resolution with a Fermi/Gauss convolution 201

B. Complementary objective lens calculations **203**
B.1. Conversion between start angle and entrance angle 203
B.2. Maximum accepted emission angle 204

Danksagungen **207**

Bibliography **224**

List of figures and tables **227**

List of own publications **231**

Curriculum Vitae **237**

List of Abbreviations **242**

Index **247**

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